

## REMARKS

Claims 48-152 are pending in the application. Claims 100-152 are withdrawn. Applicants gratefully acknowledge the withdrawal of the prior rejections of the pending claims based on WO90/15070 ("Pirrung"), WO 89/10977 ("Southern"), US 4,877,745 ("Hayes"), US 4,937,593 ("Prats"), US 3,615,240 ("Sanz") and US 5,306,510 ("Meltzer").

The Examiner has advanced new grounds of rejections. Claims 48-50, 54-57, 59, 60, 62-66, 68-76, 81, 83-92, 94 and 97-99 stand rejected as being anticipated by Brennan US 5,474,796. Claims 51-53, 58, 61, 77-80, 82, 93, and 95-96 stand rejected as being obvious over Brennan. Applicants respectfully traverse the rejections based on Brennan.

At page 3 of the office action, the Examiner states that Brennan anticipates the claimed subject matter because Brennan "teaches patterning an array using a photoresist, forming an array of 10-10000 polymers per square centimeter using 50 picoliter to 2 microliter droplets to form spots 50-2000 microns in diameter from a printer which may be formed as 64 nozzels per head with a common inlet." However, Brennan does not teach or suggest the use of a photoresist to make an array of polymers by

- (a) depositing a resist,
- (b) selectively removing a portion of the resist,
- (c) dispensing a first monomer
- (d) that is then allowed to attach to the surface of the support, and
- (e) then repeating steps (a) and (b) and then dispensing additional monomers until polymers are formed.

Instead, Brennan discloses the use of photoresists to make hydrophobic/hydrophilic derivatized array plates to which polymer are then attached. See col. 2 lines 29-43. According

to this method, the photoresist is completely removed from the array plate prior to its use to make a polymer array. In particular step (c) recites "removing the remaining photoresist".

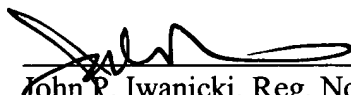
In the present method, resists are repeatedly used to expose localized areas onto which monomers are dispensed to build polymers. Nowhere does Brennan teach or suggest this aspect of the claimed invention. In fact, Brennan teaches the opposite insofar as the resist is completely removed prior to the manufacture of the polymer array.

Regarding the Examiner's belief that it would have been obvious to use known resists for their known function, Brennan's teaching away of the presently claimed invention is strong evidence that the claimed invention is not obvious. That is, one of skill in the art would not be motivated to repeatedly use the photoresist of Brennan during polymer array manufacture, given that Brennan removes the entire resist before polymer array manufacture. In fact, the Examiner has cited no reference which cures the deficiencies of Brennan.

Having addressed all outstanding issues, Applicants respectfully request reconsideration and allowance of all claims at this time. To the extent the Examiner believes that it would facilitate allowance of the case, the Examiner is invited to telephone the undersigned at the number below.

Respectfully submitted,

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